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(54) Title: EXPANDABLE ELEMENT DELIVERY SYSTEM**(57) Abstract**

Apparatus for controlling the deformation of an implant during deployment thereof, comprising: a force application mechanism for applying deforming force to the implant, by motion of a force applicator against the implant; and a restraint element positioning mechanism that positions a restraining element such that the deformation of the implant is controlled by restraint of the restraining element on allowable deformation; and a synchronizer that synchronizes the motion of the restraining element and the force applicator, to achieve a desired deformation of the implant.

